

FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: November 12, 2003 Page **1** of **3**

Applicant:	Joeri LOF et al.
Appln. No.:	Unknown
Filing Date:	November 12, 2003
Examiner:	Unknown

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	3,573,975	04/1971	Dhaka et al.	117	212	
BR	3,648,587	03/1972	Stevens	95	44	
CR	4,346,164	08/1982	Tabarelli et al.	430	311	
DR	4,396,705	08/1983	Akeyama et al.	430	326	
ER	4,480,910	11/1984	Takanashi et al.	355	30	
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GR	5,040,020	08/1991	Rauschenbach et al.	355	53	
HR	5,121,256	06/1992	Corle et al.	359	664	
IR	5,610,683	03/1997	Takahashi	355	53	
JR	5,715,039	02/1998	Fukuda et al.	355	53	
KR	5,825,043	10/1998	Suwa	250	548	
LR	5,900,354	05/1999	Batchelder	430	395	
MR	6,191,429	02/2001	Suwa	250	548	
NR	6,560,032	05/2003	Hatano	359	656	

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	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
OR	WO 99/49504	09/1999	PCT	Fukami et al.	X		X	
PR	EP 0023231	02/1981	Europe	Tabarelli et al.	X			
QR	EP 0418427	03/1991	Europe	Miyake	X		X	
RR	EP 1039511	09/2000	Europe	Murakimi et al.	X		X	
SR	DD 224448	07/1985	German	Hesse et al.		X		
TR	DD 242880	02/1987	German	Kuch		X		
UR	FR 2474708	07/1981	France	Letellier		X		
VR	JP 62-065326	03/1987	Japan	Moriuchi		X		
WR	JP 62-121417	06/1987	Japan	Nakazawa		X		
XR	JP 63-157419	06/1988	Japan	Nakasuji		X		

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YR	EP Search Report for EP 02257938 dated September 25, 2003
ZR	M. Switkes et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001
AAR	M. Switkes et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356
BBR	M. Switkes et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002

Examiner	Date Considered:
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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Page **2** of **3**

Applicant: **Joeri LOF et al.**

Appln. No.: **Unknown**

Filing Date: **November 12, 2003**

Examiner: **Unknown** Group Art Unit: **Unknown**

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	CCR	6,603,130	08/2003	Bisschops et al.	250	492.1	
	DDR	6,633,365	10/2003	Suenaga	355	53	
	EER	2002/0163629	11/2002	Switkes et al.	355	53	
	FFR	2003/0123040	07/2003	Almogy	355	69	
	GGR	2003/0174408	09/2003	Rostalski et al.	359	642	
	HHR						
	IIR						
	JJR						
	KKR						
	LLR						
	MMR						
	NNR						
	OOR						
	PPR						

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		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract	Translation Readily Available
							Enclosed	No
	QQR	JP 04-305915	10/1992	Japan	Ozeki et al.		X	
	RRR	JP 04-305917	10/1992	Japan	Ozeki et al.		X	
	SSR	JP 06-124873	05/1994	Japan	Takahashi		X	X
	TTR	JP 07-220990	08/1995	Japan	Fukuda et al.		X	
	UUR	JP 10-228661	08/1998	Japan	Kurokawa		X	
	VVR	JP 10-255319	09/1998	Japan	Suenaga et al.		X	
	WWR	JP 10-303114	11/1998	Japan	Suwa		X	X
	XXR	JP 10-340846	12/1998	Japan	Kudo		X	X
	YYR	JP 2001-091849	04/2001	Japan	Aizaki et al.		X	
	ZZR							

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AAAR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
BBBR	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			

Examiner

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CCC						
DDD						
EEE						

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FFFF						Enclosed	No Enclose No
GGG							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

HHH	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269		
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LLLR	Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003		
MMM	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36		
NNN	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309		
OOO	B.W. Smith et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003		
PPP	H. Kawata et al., "Fabrication of 0.2μm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177		
QQQ	G. Owen et al., "1/8μm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036		
RRR			
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TTT			
UUU			
VVV			
WW			
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